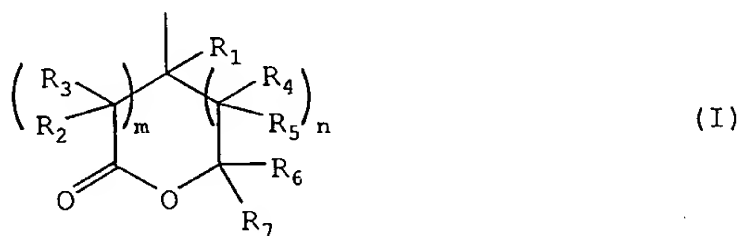


AMENDMENT UNDER 37 C.F.R. § 1.111
U.S. Appln. No. 09/620,708

(B) a resin capable of decomposing under the action of an acid to increase the solubility in alkali, containing a repeating unit represented by the following formula (AI):



wherein R represents hydrogen atom, a halogen atom, a substituted or unsubstituted alkyl group having from 1 to 4 carbon atoms, A' represents a single bond and B represents a group represented by formula (I):



wherein R₁ represents hydrogen atom or an alkyl group having from 1 to 4 carbon atoms, which may have a substituent, R₂ to R₇, which may be the same or different, each represents hydrogen atom, an alkyl group which may have a substituent, a cycloalkyl group which may have a substituent or an alkenyl group which may have a substituent, provided that at least one of R₆ and R₇ is not a hydrogen atom and R₆

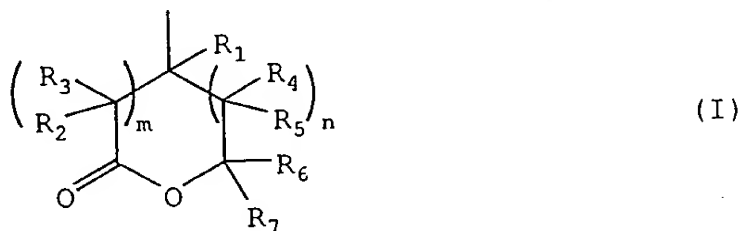
and R_7 may combine to form a ring, and m and n each independently represents 0 or 1, provided that m and n are not 0 at the same time.

9 (Amended). A positive photoresist composition for far ultraviolet exposure, comprising:

(A) a compound capable of generating an acid upon irradiation with actinic rays or radiation,

(B) a resin capable of decomposing under the action of an acid to increase the solubility in alkali, containing a repeating unit having a group represented by the following formula (I), and

(C) a fluorine-containing and/or silicon-containing surfactant:



wherein R_1 represents hydrogen atom or an alkyl group having from 1 to 4 carbon atoms, which may have a substituent, R_2 to R_7 , which may be the same or different, each represents hydrogen atom, an alkyl group which may have a substituent, a cycloalkyl group which may have a substituent or an alkenyl group which may have a substituent, provided that at least one of R_6 to R_7 is not a hydrogen atom and R_6

a² and R₇ may combine to form a ring, and m and n each independently represents 0 or 1, provided that m and n are not 0 at the same time.

18 (Amended). A positive photoresist composition for far ultraviolet exposure, comprising:

(A) a compound capable of generating an acid upon irradiation with actinic rays or radiation,

(B) a resin capable of decomposing under the action of an acid to increase the solubility in alkali, containing a repeating unit represented by the following formula (AI), and

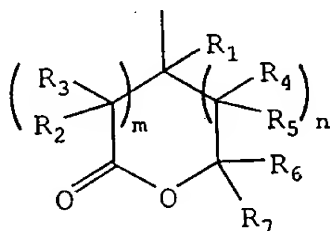
(D) a solvent containing the following solvent (a) in an amount of 60% to 90 wt % based on the entire solvent:

(a) at least one first solvent selected from propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether propionate, methyl 3-methoxypropionate, ethyl 3-methoxypropionate, methyl 3-ethoxypropionate and ethyl 3-ethoxypropionate;



AMENDMENT UNDER 37 C.F.R. § 1.111
U.S. Appln. No. 09/620,708

wherein R represents hydrogen atom, a halogen atom, a substituted or unsubstituted alkyl group having from 1 to 4 carbon atoms, A' represents a single bond and B represents a group represented by formula (I):



(I)

wherein R₁ represents hydrogen atom or an alkyl group having from 1 to 4 carbon atoms, which may have a substituent, R₂ to R₇, which may be the same or different, each represents hydrogen atom, an alkyl group which may be substituent, a cycloalkyl group which may have a substituent or an alkenyl group which may have a substituent, provided that at least one of R₆ and R₇ is not a hydrogen atom and R₆ and R₇ may combine to form a ring, and m and n each independently represents 0 or 1, provided that m and n are not 0 at the same time.